

### **Remarks/Arguments**

The Office Action of June 2, 2005 and the references cited therein have been carefully studied and reviewed, and in view of the foregoing Amendment and following representations, reconsideration is respectfully requested.

Claim 1 has been amended so as to more clearly patentably distinguish the present invention over the reference to Koshiishi et al. (USP 5,919,332). More specifically, claim 1 has been amended to recite that the insulation ring unit 170 is disposed under the focus ring 164 and yet has a protection layer coating to prevent it from being etched by plasma. On the other hand, Koshiishi et al. discloses a focus ring 119 provided with a protection layer 120. The focus ring of Koshiishi et al. can not be read on Applicant's claimed insulation ring unit 170 because the focus ring 119 is disposed only to the side of focus ring 118 and not under the focus ring 118.


Accordingly, the Koshiishi et al. reference does not anticipate claims 1 and 5 under 35 USC 102.

The reference to O'Donnell et al. (USP 6,537,429) was relied on by the Examiner for teachings therein related to particular materials that have served as protection layers. However, such teachings are not seen to overcome the deficiencies in the rejection of amended claim 1, as discussed above.

Accordingly, early reconsideration and allowance of the claims are respectfully requested.

Respectfully submitted,

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